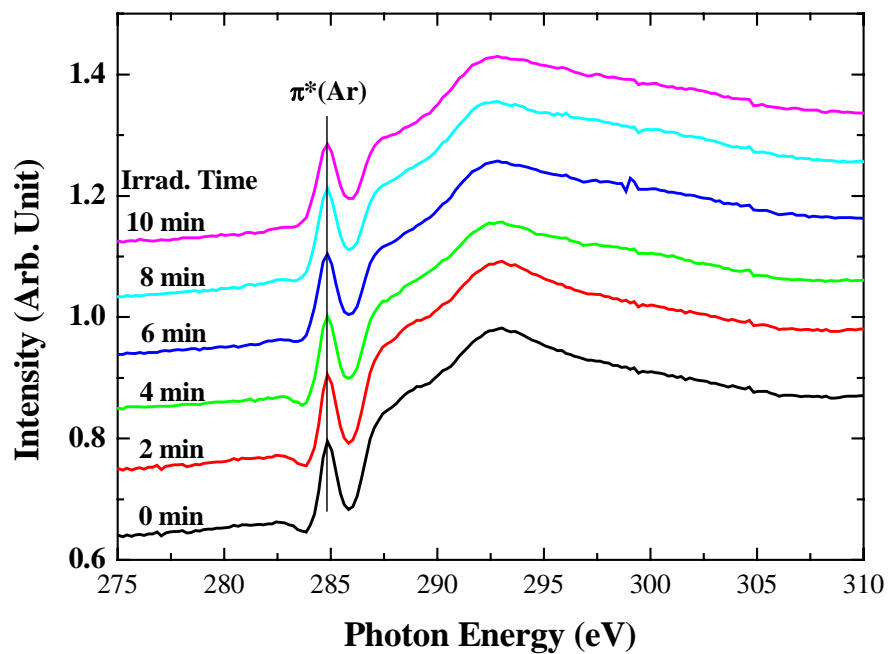
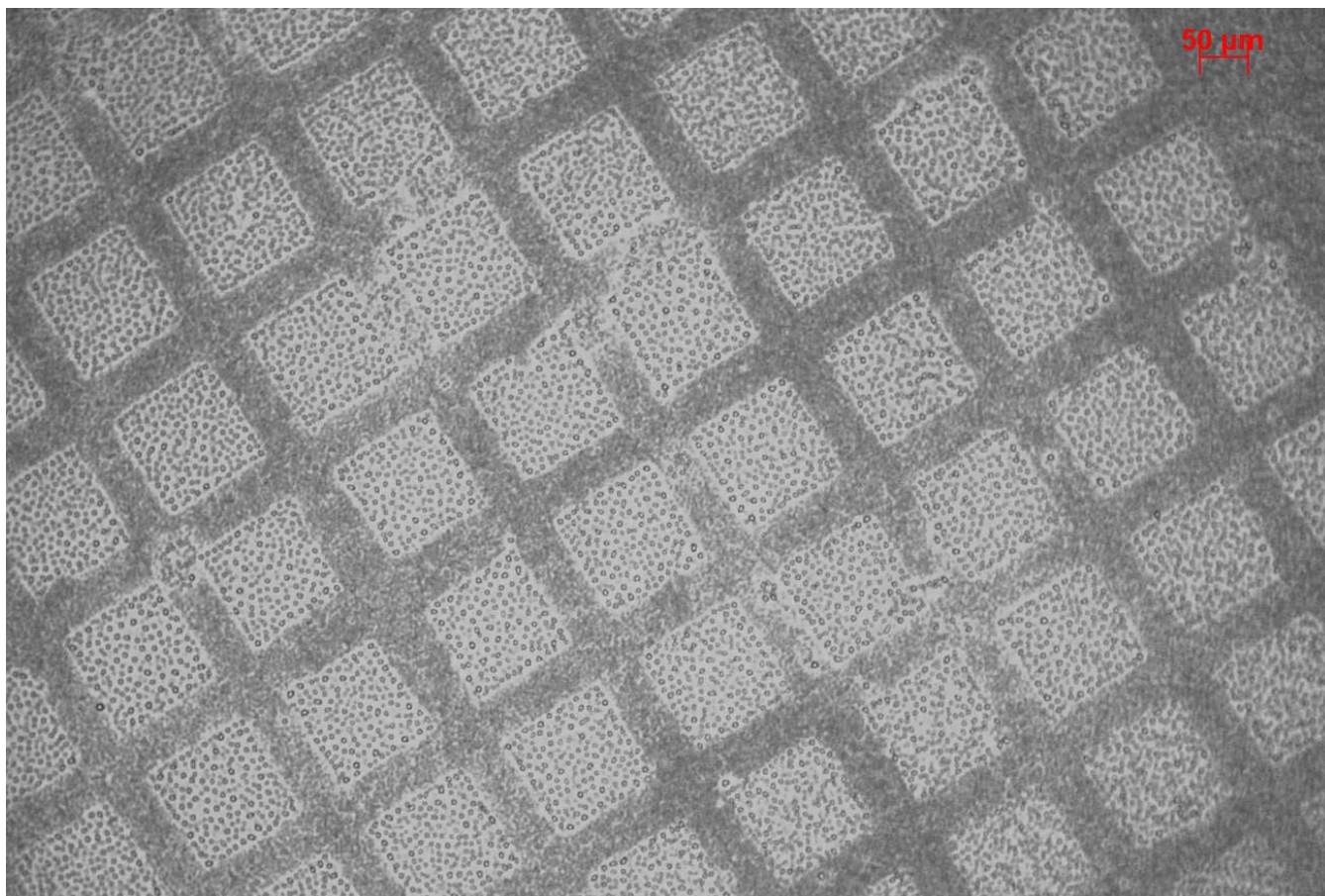


SUPPORTING INFORMATION



S1. Series of carbon K-edge NEXAFS spectra of benzaldimine monolayer irradiated by 500 eV electron beam. Each spectrum is subtracted by the spectrum of a bare silicon surface to remove substrate contribution.



S2. Optical microscopic image after spin-coating of a homopolymer blend of PS and P4VP, annealing, and removing of P4VP. For patterning, a TEM grid of 150 mesh was used as a mask. A solution of 5.0 mg/ml PS (MW 25,000) and 5.0 mg/ml P4VP (MW 15,000) in chloroform (5.0 ml) was used for spin-coating. For annealing process, the polymer coated substrate was exposed to chloroform vapor for 30 min. After then, the substrate was put into methanol for 30 min to remove P4VP selectively. Islands in the square regions were originated from inaccurate adjustment of the stoichiometry and/or incomplete removal by methanol treatment.